

Photo excited precession of magnetization in Co/Pd multilayers grown on various substrates

○K. Takahashi¹, N. Nishizawa¹, K. Nishibayashi¹, T. Matsuda¹, Y. Iwasaki¹,
Y. Kitamoto², and H. Munekata¹

Imaging Sci. & Eng. Lab., Tokyo Tech.¹ (E-mail: k.takahashi@isl.titech.ac.jp)

School of Interdisciplinary Grad. Sci. & Eng., Tokyo Tech.²

Aiming at studying novel functionality in optics and photonics with spin degree of freedom, we have been studying photo-excitation of ordered spins in weak excitation regime, and found recently that precession of magnetization could be induced in Co/Pd multilayers (MLs) grown on Si(110) with excitation power as low as $0.25 \mu\text{J}/\text{cm}^2$ at the wavelength $\lambda = 790 \text{ nm}$ [1]. Question concerning the use of a Si(110) substrate have been raised in view of substrate heating and physical property of the resultant MLs. We show here that Co/Pd MLs of similar kinds can be prepared on Si(100), GaAs(100), and GaAs(110), and discuss that the photo-excited precession of magnetization (PEPM) is not unique for samples on Si(110).

Samples consisting of $[\text{Co}/\text{Pd}]_5 / \text{Pd}(6.81\text{nm}) / \text{Ta}(2.18\text{nm})$ with different Co and Pd layer thicknesses, Co/Pd in the unit of nm, were prepared on various Si and GaAs substrates using DC magnetron sputtering at the substrate temperature of $150 \text{ }^\circ\text{C}$. All samples have exhibited perpendicular magnetic anisotropy at room temperature (RT). PEPM experiments were carried out by time-resolved magneto-optical spectroscopy on the basis of pump and probe technique using a mode-locked Ti:sapphire laser of 150-fs pulse width at the wavelengths $\lambda = 790 \sim 895 \text{ nm}$.

Temporal profiles of magneto-optical (MO) signals obtained at $\lambda = 790 \text{ nm}$ ($P_{\text{pump}} = 1.5 \mu\text{J}/\text{cm}^2$) are shown in Fig.1 (a) for samples grown on four different substrates. Oscillations due to PEPM are observed in all samples. Shown in Fig.1 (b) is a MO temporal profile for the sample grown on GaAs(100) obtained at $\lambda = 890 \text{ nm}$ ($P_{\text{pump}} = 18 \mu\text{J}/\text{cm}^2$) which is longer than the fundamental absorption edge ($\lambda_{\text{GaAs}} = 872 \text{ nm}$) of the substrate. This fact indicates that PEPM is attributed solely to light absorption in MLs. Shown in Figs.2(a)-(c) are static optical data for the 0.45/0.57 MLs sample grown on GaAs(100), from which we are able to derive complex refractive index $n = 2.7 + 3.8i$, together with dielectric tensor $\epsilon_{xx} = -7.15 + 20.52i$ and $\epsilon_{xy} = 0.0836 - 0.0362i$. Magnitudes of real and imaginary parts of the off-diagonal term appear to be, respectively, five times smaller and six times larger than those of representative MO materials [2].

[1] K.Yamamoto *et al.*, IEEE Trans Mag. **49**, 7 (2013). [2] M. Mansuripur, JAP **67**, 6466 (1990).

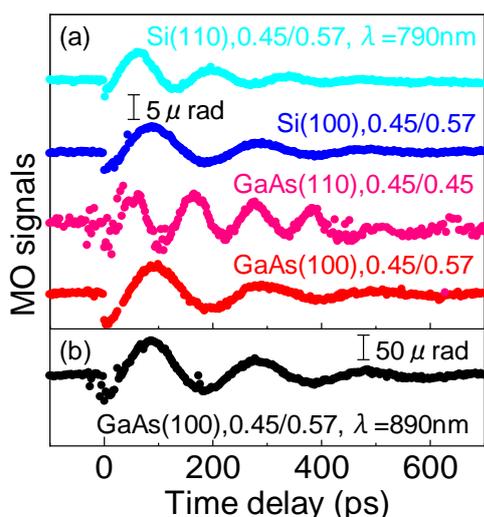


Fig.1: (a) Four temporal profiles obtained at RT with $\lambda = 790 \text{ nm}$ and $P_{\text{probe}} = 0.3 \mu\text{J}/\text{cm}^2$ from the samples grown on, from the top, Si(110), Si(100), GaAs(110), GaAs(100). (b) A temporal profile obtained at RT with $\lambda = 890 \text{ nm}$ and $P_{\text{probe}} = 0.3 \mu\text{J}/\text{cm}^2$ from the samples grown on GaAs(100). Non-oscillatory backgrounds are subtracted from the data.

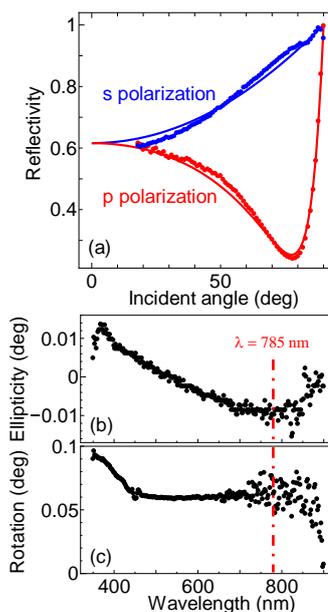


Fig.2: Three static optical data at RT: (a) dependence of incidence angle of light on reflectivity measured at $\lambda = 785 \text{ nm}$. Lines represent calculated curves using Fresnel equation. (b) ellipticity and (c) polar Kerr spectra measured with $H_{\perp} = 10 \text{ kOe}$.